

Update to Radiation Effects in GaN

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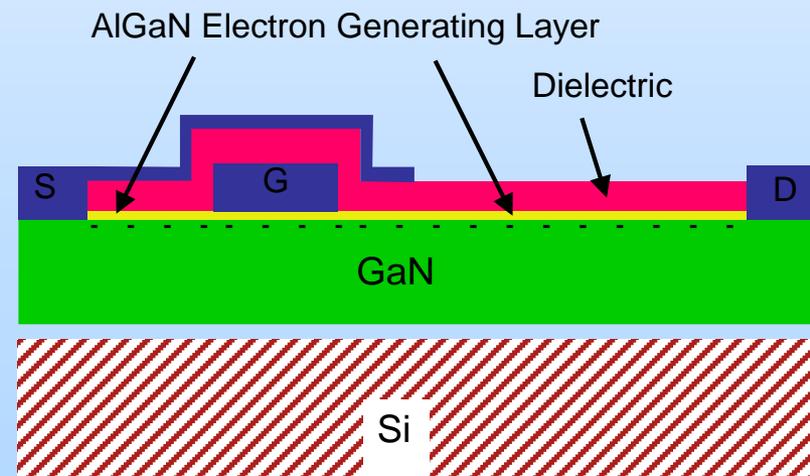
Previous body of knowledge on GaN

- **Current silicon power solutions are at their innate limits for space applications**
 - Silicon devices are at efficiency limit
 - Best hi-rel devices are less than ~400 V drain-to-source
- **GaN devices are becoming available**
 - Reliability effects are a concern
 - Gate stress is limited (abs max of $V_{gs} +6, -5$ V)
 - Thermal effects and aging are under study at GRC

200V Silicon Device
(30 milli Ohms)

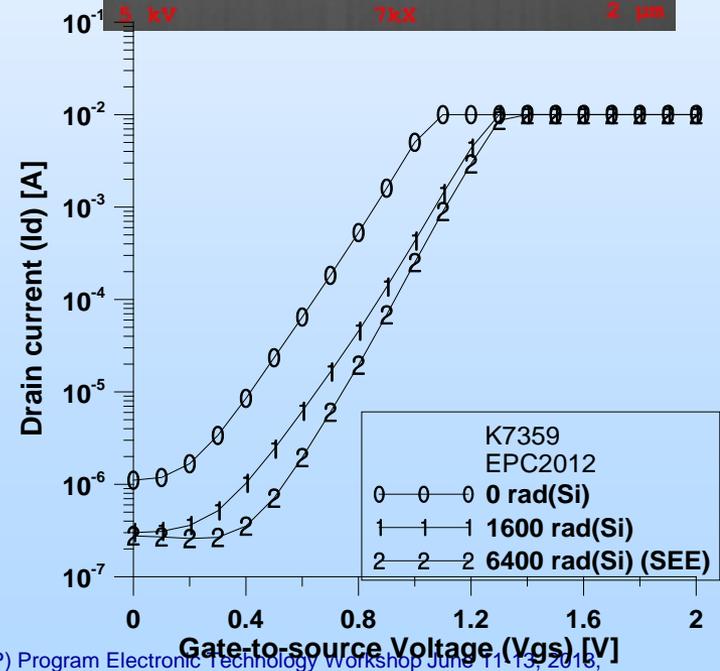
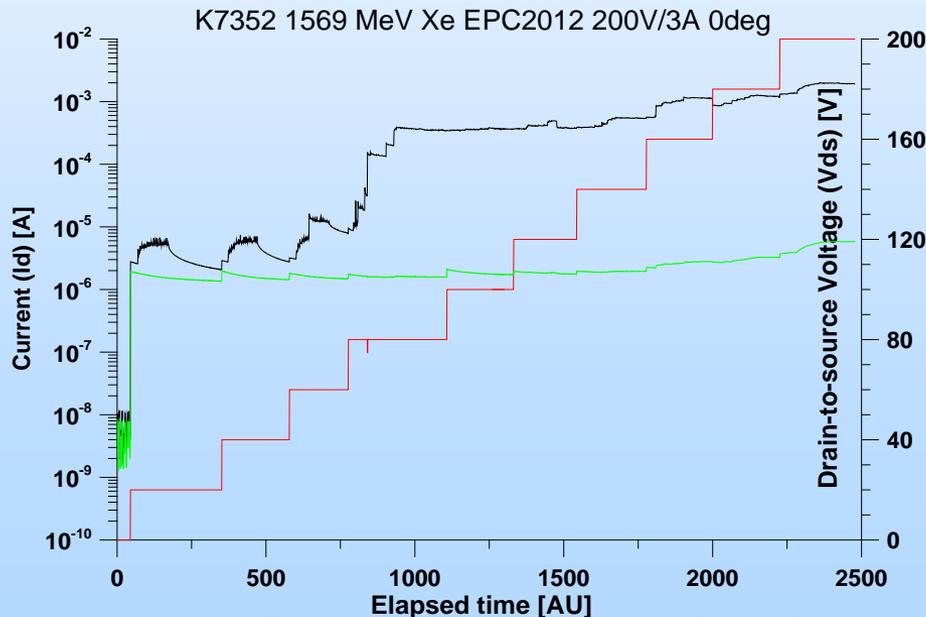
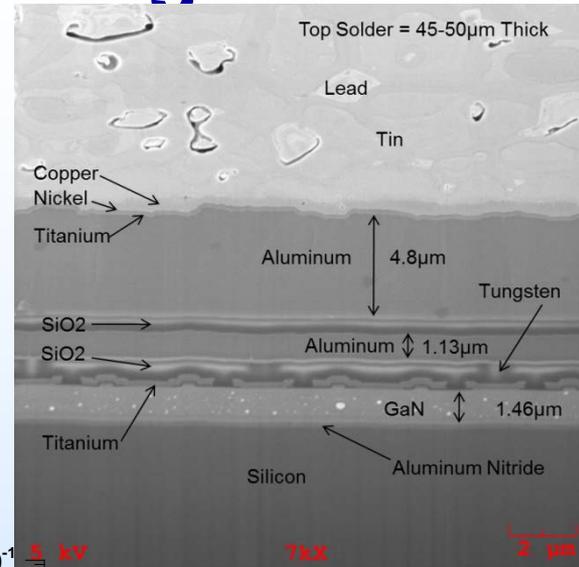


200V GaN Device
(25 milli Ohms)



Previous body of knowledge on GaN

- SEEs in GaN have been observed
- Used the NEPP guideline: **The Test Guideline for Single Event Gate Rupture (SEGR) of Power MOSFETs [JPL Publication 08-10 2/08]**
 - No post irradiation stress tests between
 - Testing at angle required





Previous body of knowledge on GaN

- **Devices with lower voltage rating were less susceptible to dose damage**
- **At normal incidence, the higher LET ion does more damage**
 - **Devices irradiated at 60° tilt showed little degradation**
 - **Devices irradiated at 60° roll showed some degradation**
- **Gen2 parts were more robust than Gen1**

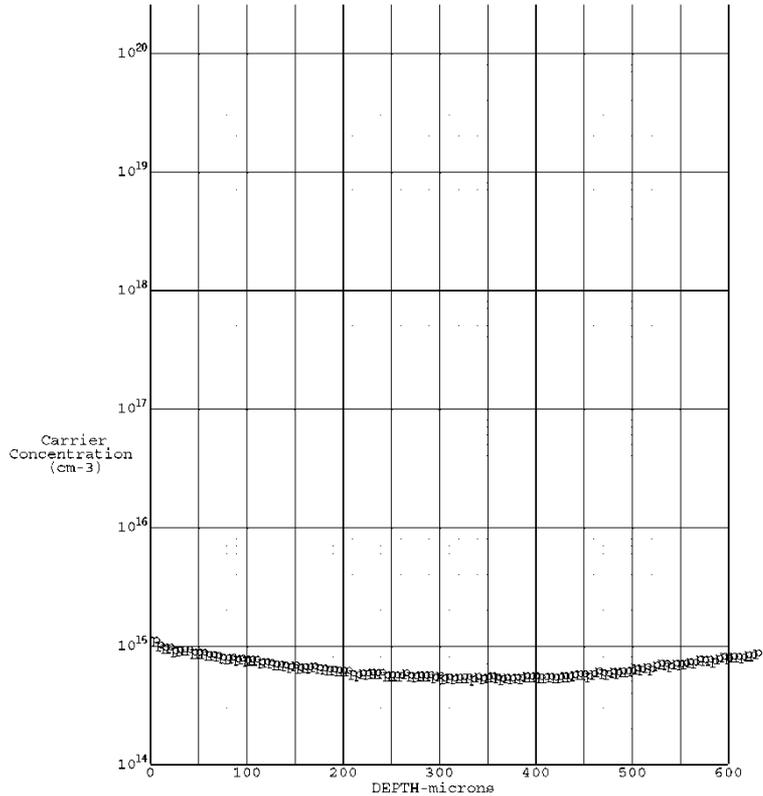
V_{SEE} for GaN for all $V_{gs} < V_{th}$

Vds [V]	Gen 1 V_{SEE} [V]	Gen 1 V_{SOA} [V]	Gen 2 V_{SEE} [V]	Gen 2 V_{SOA} [V]
40	40	30	40	30
100	40	30	60	45
200	40	30	80	60



Spreading resistance measurement

EPC1012

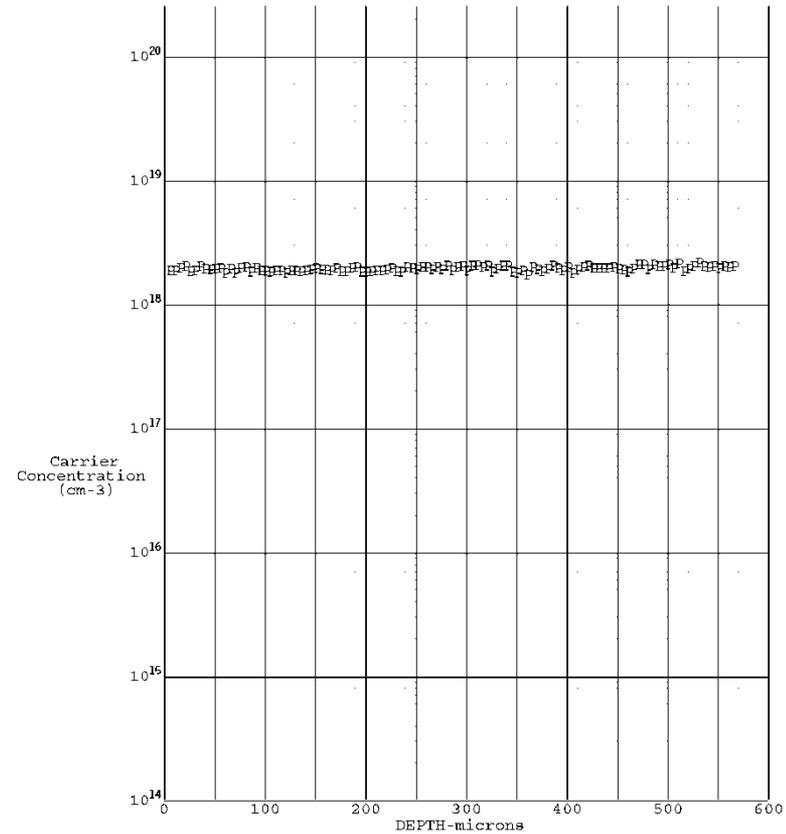


Date	03/25/13	Probe Load	2.6 grams	Orientation	<100> Si
File #	RNEJ1758	Bevel Angle	0.9999	Step Inccn	5 um
Source	JET PROPULSION			Sample #	#1012
Job #	1303080				
Profile by	Leo				



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EPC2012



Date	03/25/13	Probe Load	2.6 grams	Orientation	<100> Si
File #	RNEJ1767	Bevel Angle	0.9999	Step Inccn	5 um
Source	JET PROPULSION			Sample #	#2012
Job #	1303080				
Profile by	Leo				



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To be presented at the 4th NASA Electronic Parts and Packaging (NEPP) Program Electronic Technology Workshop June 11-13, 2013, NASA GSFC, Greenbelt, MD.



Current investigations

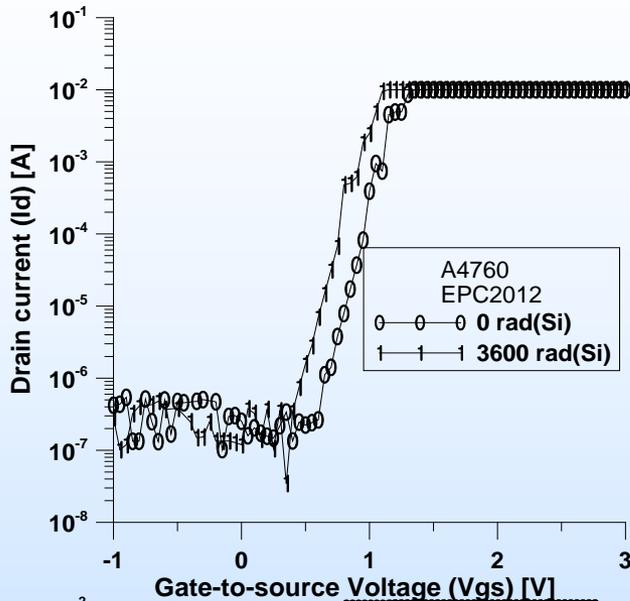
- **Proton damage**
 - Upper limit for damage
 - SEE from spallation reactions
 - Tungsten in device structure will generate secondaries in that may replicate SEE effects
- **Recommended testing/assurance methods**
 - 1080 test circuit
 - Prioritization of test matrix
 - Ion conditions
- **Failure mechanism identification**
 - Failures manifesting in drain-to-source leakage have been seen
 - Role of isolation oxide under scrutiny
 - Failures in gate-to-source leakage have been seen
- **EPC1012 and EPC2012 are the most sensitive and therefore the best candidates**



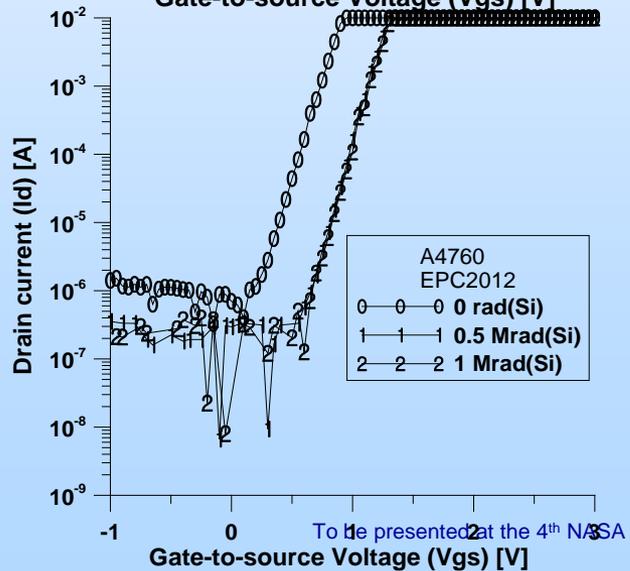
PROTON EFFECTS

Proton testing results

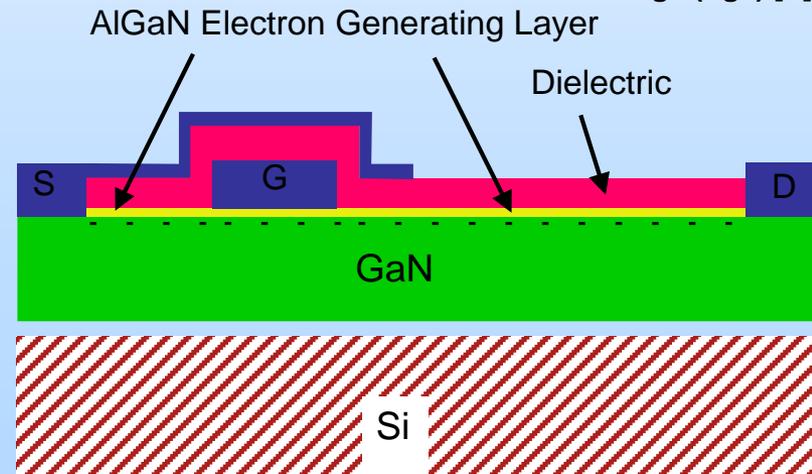
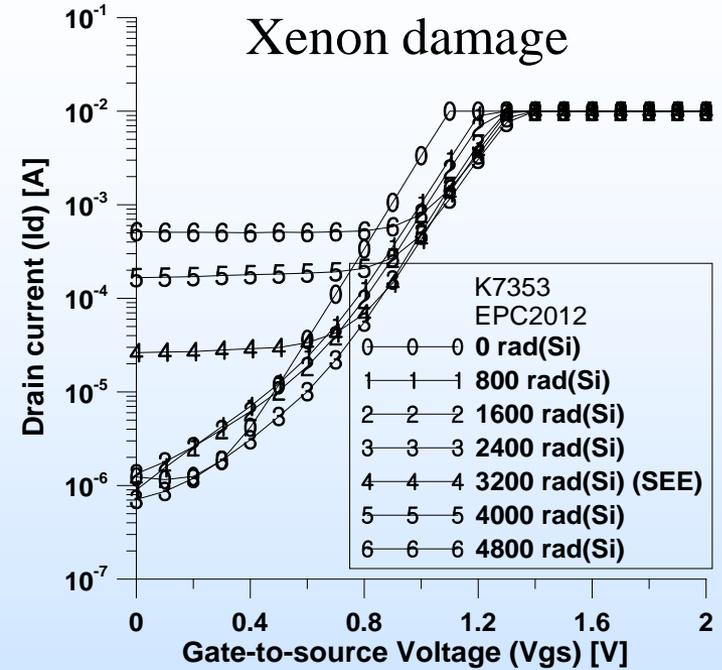
Proton damage



No SEE from protons.



Xenon damage

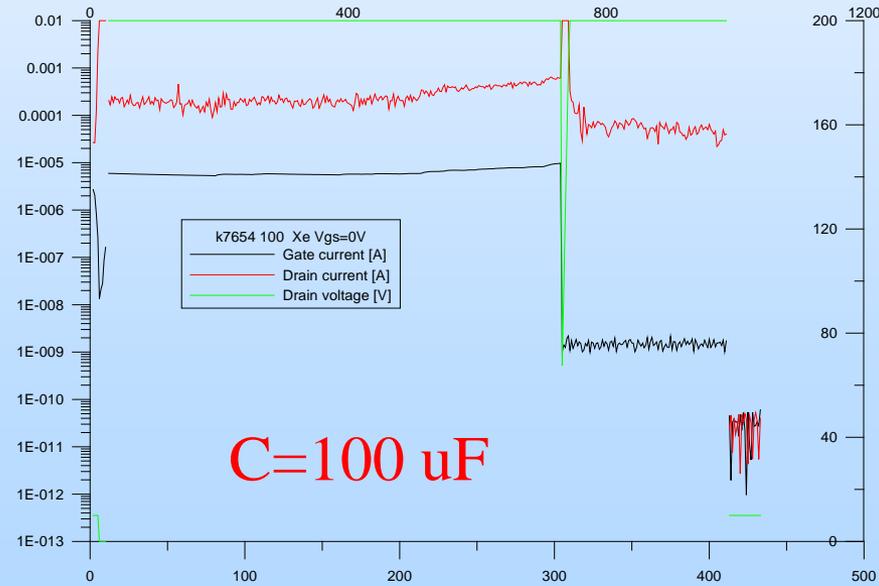
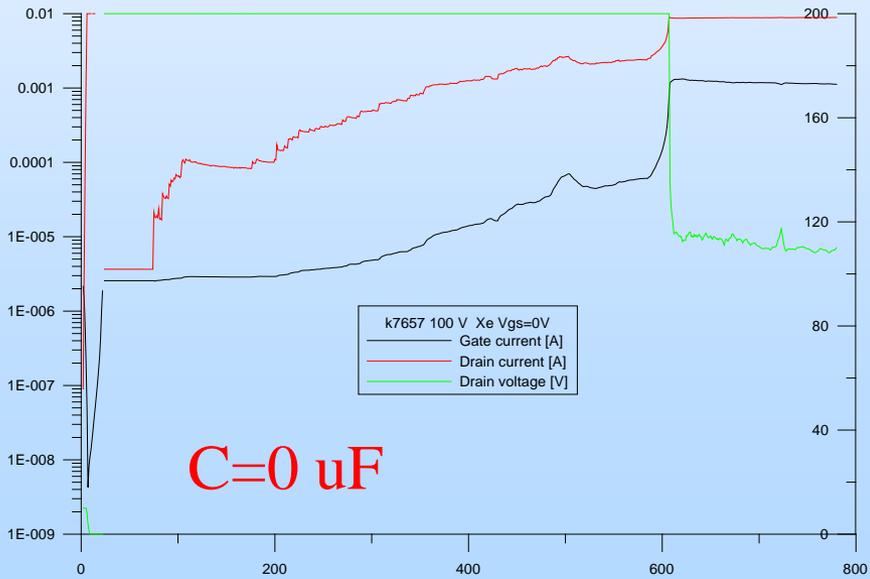
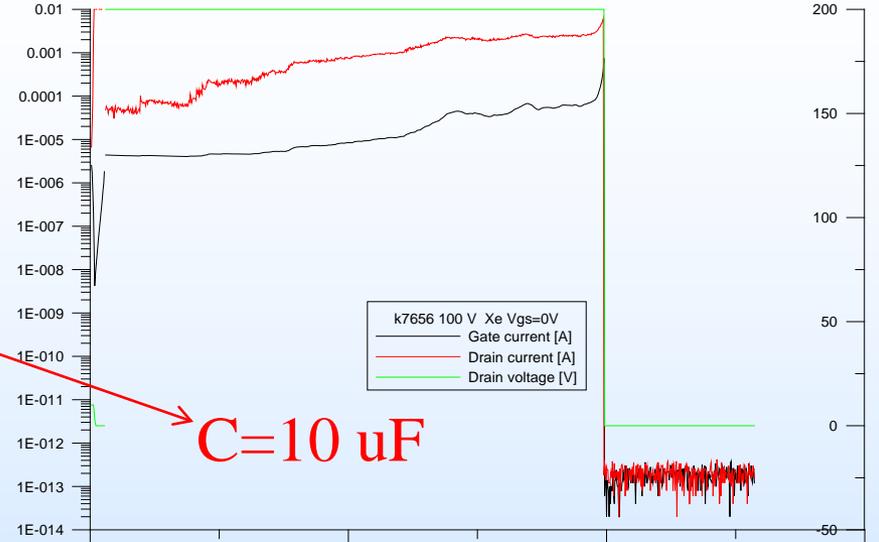
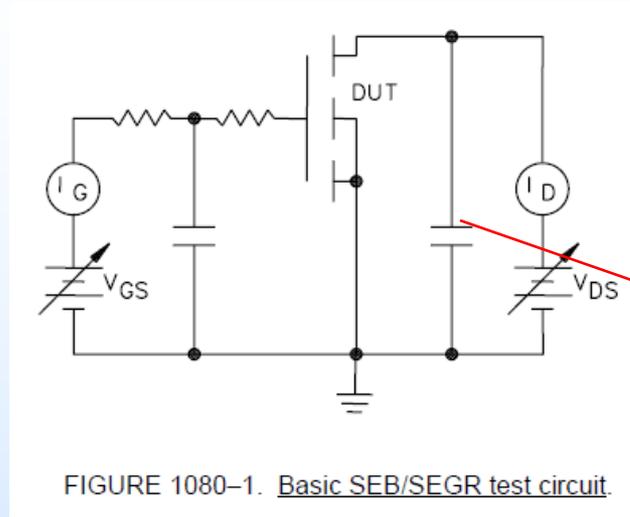




BEST TEST METHODS

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Effect of 1080 test circuit



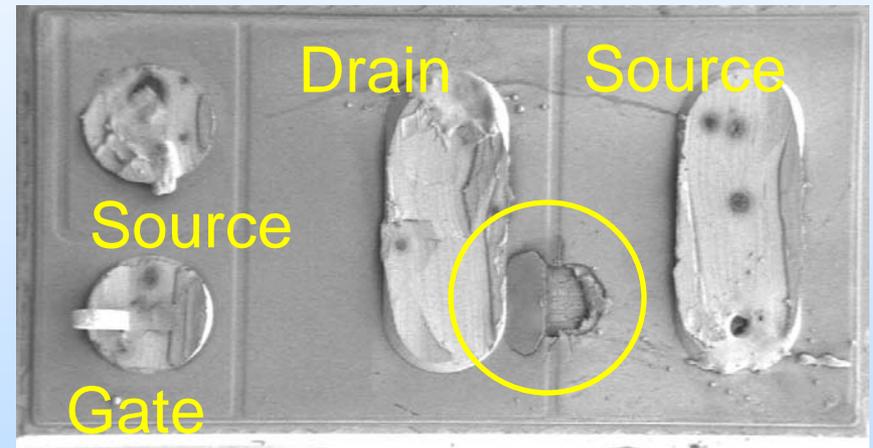
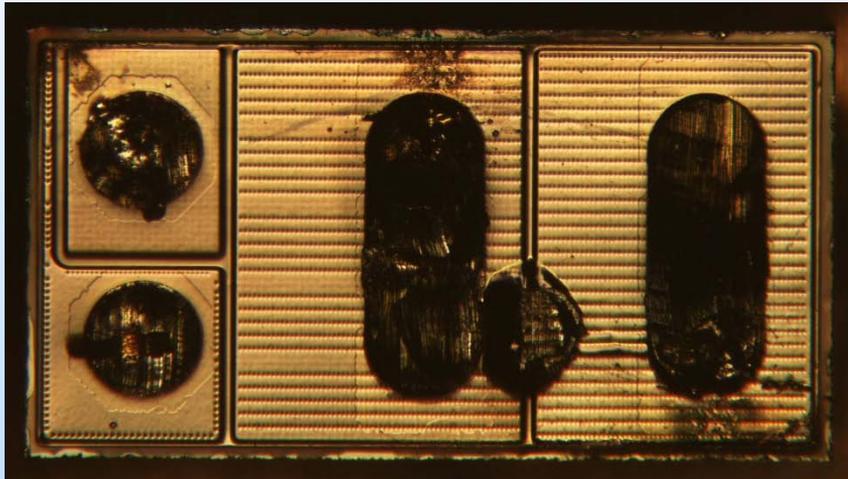


FAILURE ANALYSIS

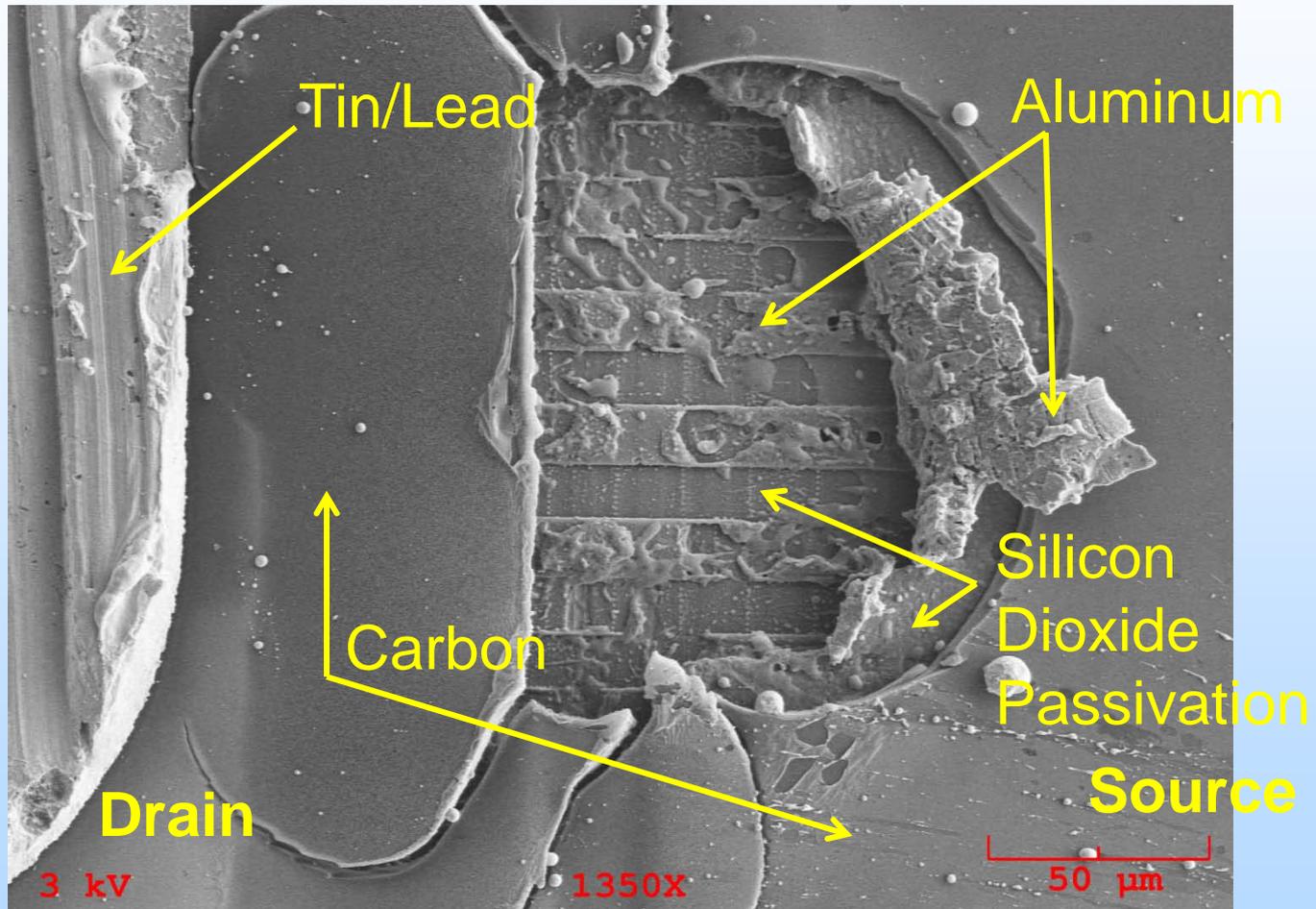
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Optical and SEM of EPC2012

Circle Encompassing Damaged region



Closer SEM View of Drain to Source Damaged Region for EPC2012





Conclusion

- **Proton damage**
 - DDD and proton SEE apparently not an issue for GaN
 - Observed effects may be architecturally dependent
- **Recommended testing/assurance methods**
 - Stiffening capacitance is recommended for worst case
- **Failure mechanism identification**
 - Isolation oxide is the drain-to-source path
 - SEE mechanism under study
- **Future work**
 - Identification of the SEE mechanism with follow on modeling
 - Include angle, ion-energy, and bias effects
 - Gate SET and RF testing